

Dimension XR Scanning Probe Microscopes

Extreme Research Systems for Nanomechanics, Nanoelectrical, and Nanoelectrochemistry

Innovation with Integrity

Atomic Force Microscopy

Enabling First-and-Only AFM Capabilities and Performance

Bruker's Dimension XR scanning probe microscope (SPM) systems incorporate decades of research and technological innovation to deliver the utmost performance, functionality, and capability in nanoscale investigation. The extreme research (XR) family of SPMs for FastScan® and Icon® AFM platforms provides unique packaged solutions for advanced research in nanomechanical, nanoelectrical, and nanoelectrochemical characterization. Quantification of materials and active nanoscale systems in air, fluid, and electrical or chemically reactive environments has never been easier.

Three distinct Dimension XR configurations, available on either a FastScan or Icon AFM platform, provide advanced research capabilities in optimized packages:

XR Nanomechanics

- Provides a range of modes to comprehensively detect the smallest structures with spatial resolution down to sub-molecular units of polymer chains
- Enables correlative nanomechanics characterization to bulk DMA and nanoidentation methods with NEW AFM-nDMA[™] mode
- Performs quantifiable nanoscale characterization extending from soft sticky hydrogels and composites to stiff metals and ceramics

XR Nanoelectrical

- Covers the broadest array of electrical AFM techniques in a single system
- Provides electrical spectra in every pixel correlated with mechanical property measurements with NEW DataCube modes
- Delivers previously unattainable information from a single measurement

XR Nanoelectrochemical

- Enables robust AFM-based scanning electrochemical microscopy (AFM-SECM) and electrochemical AFM (EC-AFM)
- Acquires electrochemical information with <100 nm spatial resolution
- Performs simultaneous electrochemical, electrical, and mechanical mapping in solution

Complete Characterization with Highest Spatial Resolution

With thousands of peer-reviewed scientific papers around the world, the large-sample Icon and FastScan AFMs have helped change the landscape of both atomic force microscopy and materials science. The new Dimension XR configurations of these legendary platforms take the fullest advantage of the over 30 years of AFM innovation to enable out-of-the box tailored characterization for breakthrough nanomechanics, nanoelectrical, and nanoelectrochemical research. Whichever platform and configuration you choose, you will benefit from the highest performance features and latest technological advances in the industry, along with the highest measurement reproducibility and easiest workflow of any commercial AFM.

Dimension Icon is the world's most utilized large-sample AFM platform, featuring industry-leading application flexibility, exceptional performance, and productivity:

- Unmatched flexibility via measurement modes and correlative techniques for large, small, or multiple samples, all on a single AFM platform
- Highest performance and repeatability with lowest noise and drift, proven through a vast publication record of scientific discovery and development of innovative materials
- Exceptional productivity, from one to multiple samples, with fast scanning and automated measurement recipes for thousands of unattended measurements into preconfigured settings



Dimension FastScan is the industry standard for the ideal balance of scan speed, resolution, accuracy, drift and noise, making fast scanning atomic force microscopy a practical commercial reality:

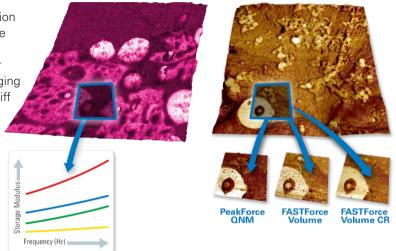
- Incorporates all the benefits of Dimension Icon with use of Icon scan head
- Fastest scanning rates in air and fluid, with automated laser and detector alignment, comprehensive work flow, and "smart engaging" for unprecedented productivity
- High resolution and long tip-life via the industry's most precise force control at the tip



Quantitative Analysis for Nanomechanical Applications

The **Dimension XR Nanomechanics** configuration for Icon and FastScan AFM systems provides the complete set of capabilities necessary to rapidly and quantitatively characterize materials for their nanomechanical characteristics, on samples ranging from soft, sticky hydrogels and composites to stiff metals and ceramics.

The XR Nanomechanics bundled solution encompasses the full evolution of nanoscale AFM nanomechanical measurement techniques, including Bruker's new, revolutionary AFM nano-dynamic mechanical analysis. This is the first and only AFM solution that ties to bulk DMA.



AFM-nDMA

Revolutionary AFM-nDMA

For the first time an AFM can provide complete and quantitative viscoelastic analysis of polymers at the nanoscale, probing materials at rheologically relevant frequencies, in the linear regime. Proprietary dual-channel detection, phase-drift correction, and reference frequency tracking enable a small strain measurement in the rheologically relevant 0.1 Hz to 20 kHz range for nanoscale measurements of storage modulus, loss modulus, and loss tangent that tie directly to bulk DMA.

Exclusive PeakForce QNM

Quantitative characterization of nanomechanical properties—including modulus, adhesion, dissipation, and deformation — while simultaneously imaging sample topography at atomic-scale resolution has become a routine endeavor with this mode. Now Bruker's frequency-calibrated probes enable defined geometry and adhesion to track probe-sample contact with the lowest uncertainty in measurements of sticky-soft materials in the <1 kPa to 100 GPa range, while rendering results with high-resolution nanoscale mapping.

FASTForce Volume

This mode extends the operating frequency of linear ramps by >400 Hz, closing the frequency gap between PeakForce QNM and standard Force Volume mapping. The overlap of operating frequencies facilitates nanomechanical correlative studies between modes, rendering greater measurement confidence while allowing investigation of property material frequency dependency.

Innovative FASTForce Volume CR

Due to its ability to measure a wide range of moduli, contact resonance is a powerful tool for nanomechanical measurements. However, until now, its implementation has been hampered by contact mode's limitations, including slow imaging speed, complex analysis, and the requirement of specialized hardware for full spectrum acquisition. XR Nanomechanics resolves these issues, providing consistent data of both elastic and viscoelastic properties.

Quantifies force
 Tracks and quantifies adhesion
 Requires no reference sample

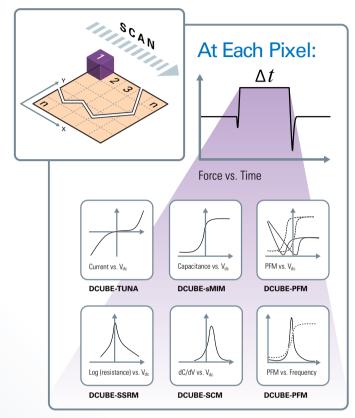
Multi-Dimensional Nanoelectrical Characterization

The Dimension XR Nanoelectrical configuration for Icon and FastScan AFM systems includes the most complete array of electrical AFM techniques on a single system. PeakForce TUNA[™] and PeakForce KPFM[™] have already built an impressive publication record of expanding materials research, from conventional contact-based electrical modes to correlative electrical and mechanical data. Now, Bruker's new DataCube modes provide multidimensional nanoscale information at every pixel, simultaneously capturing in a single measurement both electrical and mechanical characteristics.

Proprietary DataCube Modes

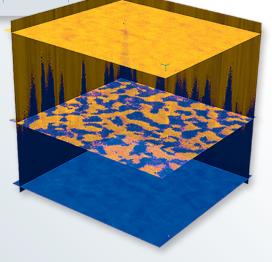
These modes utilize FASTForce Volume to perform a force-distance spectrum in every pixel, with a user-defined dwell time. Using high data capture rates, a multitude of electrical measurements are performed during the dwell time, resulting in electrical and mechanical spectra at every pixel. DataCube modes provide full characterization in a single experiment, which is unheard of in a commercial AFM.

Nanoelectrical modes



Techniques	Conductivity	Impedance	Carrier Density	Piezoelectricity	Local EC Activity	Potential/ Field	
DataCube Mode	DCUBE-TUNA DCUBE-CAFM DCUBE-SSRM	DCUBE-sMIM	DCUBE-SCM DCUBE-sMIM DCUBE-SSRM	DCUBE-PFM DCUBE-CR-PFM	DCUBE-SECM	DCUBE-EFM	
PeakForce Tapping (PF)	PF-TUNA	PF-sMIM	PF-sMIM		PF-SECM	PF-KPFM	
Tapping Mode		sMIM				EFM KPFM	
Contact Mode	TUNA C-AFM SSRM	sMIM	SCM sMIM SSRM	PFM	SECM		

A DCUBE-PFM measurement clearly shows the domains flipping at different potential levels for each discrete pixel on a BiFeO₃ thin film.



Highest Resolution Scanning Electrochemical Imaging

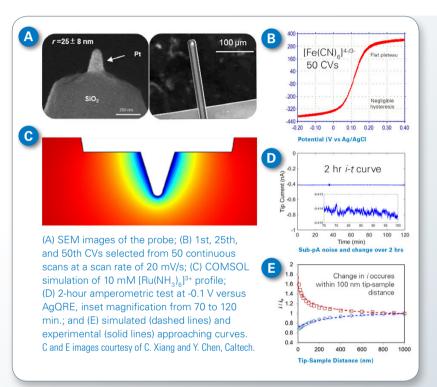
The **Dimension XR Nanoelectrochemical** (NanoEC) configuration for Icon and FastScan AFM systems provides a turnkey solution for real-time quantitative analysis of electrochemical reactions. These systems utilize EC-AFM and PeakForce SECM[™] modes to perform in-situ topography scans in the electrochemical cell, and are specifically designed for long-term in situ electrode studies under electrochemical control and in volatile solvents.

Exclusive PeakForce SECM

With a spatial resolution less than 100 nm, this mode redefines what is possible in the nanoscale visualization of electrical and chemical processes in liquid. PeakForce SECM dramatically improves, by orders of magnitude, the resolving power over traditional approaches. This enables entirely new research into energy storage systems, corrosion science and biosensors. opening the door to novel measurements on individual nanoparticles, nanophases, and nanopores. Only, PeakForce SECM provides simultaneous capture of topographic, electrochemical, electrical, and mechanical maps with nanometer-scale lateral resolution.

Bruker's premounted PeakForce SECM probes offer easy and safe handling, and the optimized holder delivers an electrically stable architecture for sensitive signal processing. Extremely stable probe performance has been demonstrated for over 10 hours of EC testing and multiple reuse cleaning cycles.

07-06



Dimension XR AFMs with proprietary probe positioning and the exclusive SECM nanoelectrode make <100 nm EC mapping a reality. Your research deserves the highest spatial resolution routinely achievable by a commercial solution.

Unlimited Flexibility to Expand Your Research

Any Dimension XR configuration you chose for your research enables the addition of many other a la carte capabilities to further tailor your system for your exact application needs, now and in the future. Combined with our many proprietary AFM techniques, modes, and mode enhancements, the Dimension XR systems provide the unique capabilities that can take your nanoscale research to the next level.

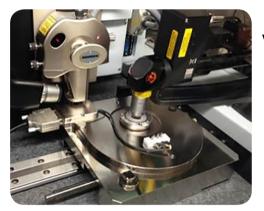
wort nanoscope as ns wort numpy as np wn nanoscope import files wn nanoscope.constants import FORCE, METRIC, VOLTS, PLT_kwargs

sme = "DCUBE_TUNA_Iron_Oxide.spm"
th = "C:\\Users\\ DataCubesPFM \\Desktop\\codes\\" + fname
le_ = ns.files.ForceVolumeHoldFile(path)
le_.open()

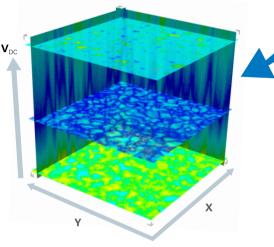
res = file_[0].number_of_lines
l = file_[0].samples_per_line
ld_len = len(file_[3].get_force_hold_data(0, METRIC))

tacube = np.zeros((lines, spl, hold_len))
 i in range(lines):
 for j in range(spl):

Software toolboxes for MATLAB and Python, along with custom programming tools, offer exceptional flexibility while maintaining ease of use in multi-user environments.



Open-platform hardware customization, limited only by your imagination, adapts to most environments and enables the highest performance available in a commercial AFM.





More Modes for Higher Productivity

- Contact Mode
- PeakForce Tapping®

PhaseImaging™

ScanAsyst®

TappingMode™ AFM-nDMA[™]

Contact Resonance (FFV-CR)

Fast-Force Volume (FFV)

Force Modulation™ (FMM)

HarmoniX®

Lateral Force Microscopy (LFM)

Nano-Indentation

PeakForce QNM®

Dark Lift

DataCubes: DCUBE-TUNA DCUBE-SSRM DCUBE-SCM DCUBE-SMIM DCUBE-PFM DCUBE-CR-PFM

Electrostatic Force (EFM)

LiftMode™

Magnetic Force (MFM)

PeakForce KPFM™

PeakForce sMIM™

PeakForce SSRM™

PeakForce TUNA™

Piezo Response (PFM)

Scanning Capacitance (SCM)

Scanning Spreading Resistance (SSRM)

STM AFM-SECM (PF-SECM) Electrochemistry (EC-AFM)

Dimension XR Configurations							
		XR Nanomechanics	XR Nanoelectrical	XR NanoEC			
	AFM nanoDMA (0.1 - 300 Hz)	•	0	0			
Nanomechanics capabilities	RampScripting	•	0	0			
	MIROView	•	0	0			
Nanoelectrical capabilities	PeakForce TUNA (CAFM)	0	٠	0			
	DataCube TUNA	0	٠	0			
	PeakForce KPFM	0	•	0			
	Dark Lift	0	•	0			
	Electrical TUNA in Liquid	0	٠	0			
Nano- electrochemical capabilities	PeakForce SECM /Electrochemistry	0	0	•			
	DataCube SECM	0	0	•			
Other features	Icon FastTapping	•	٠	•			
	SAMV	•	•	•			

Legend: Standard

Optional
O

Dimension XR Specifications

Icon Scan HeadFastScan Scan HeadX-Y Scan Range (µm)≥90 × 90≥35 × 35Z Range (µm)≥12≥3Vertical Noise Floor - RMS/Adev (pm)≤30/25, height in appropriate environment, typical imaging BW (≤625 Hz)≤40/32, sensor in appropriate environment (≤625 kHz)X-Y Position Noise - RMS/ Adev, Closed-Loop (pm)≤125/100≤145/116Z Sensor Noise - RMS/Adev (pm)≤20/15 typical imaging BW (≤625 Hz)System Drift210 mm vacuum chuck for samples U (≤625 Hz)System Drift210 mm vacuum chuck for samples Jumm in diameter, ≤15 mm thickMotorized Position150 × 180 mm inspectable arrewith manually rotating chuck; 2 µm repeatability, unidirectionalOpticsAuto focus and digital zoom; < 1 µm resolution; 180 to 1465 µm viewing area							
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Vertical Noise Floor - RMS/Adev (pm)<30/25, height in appropriate environment, typical imaging BW (<625 Hz)	X-Y Scan Range (µm)	≥90 × 90	≥35 x 35				
- RMS/Adev (pm) typical imaging BW (≤625 Hz) environment (≤625 kHz) X-Y Position Noise - RMS/ Adev, Closed-Loop (pm) ≤125/100 ≤145/116 Z Sensor Noise - RMS/Adev (pm) ≤20/15 typical imaging BW (≤625 Hz) ≤145/116 System Drift ≤20/15 typical imaging BW (≤625 Hz) ≤625 Hz) Sample Size / Holder 210 mm vacuum chuck for samples ≤210 mm in diameter, ≤15 mm thick Motorized Position 150 × 180 mm inspectable area with manually rotating chuck; 2 µm repeatability, unidirectional Optics Auto focus and digital zoom; <1 µm resolution; Auto focus and digital zoom; <1 µm resolution;	Z Range (µm)	≥12	≥3				
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Miotorized Position 2 μm repeatability, unidirectional; 3 μm repeatability, bidirectional Δμto focus and digital zoom; Auto focus and digital zoom; Optics <1 μm resolution;	Sample Size / Holder	210 mm vacuum chuck for samples \leq 210 mm in diameter, \leq 15 mm thick					
Optics <1 µm resolution; <1 µm resolution;	Motorized Position						
	Optics	<1 µm resolution;	<1 µm resolution;				
EH&S CE Certified	EH&S	CE Certified					

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